

L Number	Hits	Search Text	DB	Time stamp
2	50	Argon and ((ion adj mill) same etching)	USPAT	2003/02/27 09:49
3	0	L-shaped adj spacer and CH3F and O2 and anisotropically	USPAT	2003/02/27 09:49
4	0	L-shaped adj spacer and CH3F and O2	USPAT	2003/02/27 09:50
5	0	(L-shaped adj spacer) and CH3F and O2	USPAT	2003/02/27 09:50
6	8	(L-shaped adj spacer) and anisotropically	USPAT	2003/02/27 10:05
7	0	((L-shaped adj spacer) and anisotropically) and CH3F	USPAT	2003/02/27 10:06
8	1	((L-shaped adj spacer) and anisotropically) and chlorine	USPAT	2003/02/27 10:13
15	508	438/595.cccls.	USPAT	2003/02/27 10:19
16	0	438/595.cccls. and CH3F	USPAT	2003/02/27 10:19
17	67	438/595.cccls. and (fluorine or chlorine or O2)	USPAT	2003/02/27 10:20
18	15	438/595.cccls. and (fluorine or chlorine or O2).clm.	USPAT	2003/02/27 10:20
19	8	(438/595.cccls. and (fluorine or chlorine or O2).clm.) and spacer	USPAT	2003/02/27 10:20
20	0	6391732.URPN.	USPAT	2003/02/27 10:23